Supplementary Information

for

Anti-ambipolar and Photovoltaic effect in

p-MoTe₂/n-InSe Heterojunctions

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Figure Caption

Figure S1. XRD pattern of β -InSe.

Figure S2. PL spectra of the InSe/MoTe₂ heterostructure.

Figure S3. Calculated band edges of single-layer and InSe and MoTe₂ with respect to the vacuum level.

Figure S4. Schematic illustration of PVA transfer methods.

Figure S5. (a-b) Transfer characteristic of InSe and MoTe₂ with different thickness.

Figure S6. I_{ds} - V_{ds} curves of the MoTe₂/InSe anti-ambipolar transistors with different V_{ds} .

Figure S7. I_{ds} - V_{ds} characteristics of the detector in different light intensities at 635 nm.

Figure S8. (a) I–t curves of the device under light intensities 405 and 635 nm without biase for longtime.

Figure S9. I–t curves of the device under various biases with light wavelength at 635 nm.



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